

TITLE OF INVENTION: COMPOSITION FOR FORMING SILICON-
CONTAINING FILM, METHOD FOR FORMING FILM, AND SUPER
STRAIGHT

ABSTRACT

The present invention is a composition for forming a silicon-containing film, the composition including a condensation-reactive thermally curable silicon-containing material (Sx) being a polysiloxane resin, wherein the material (Sx) has an organic group that forms a diol structure with a plasma treatment, the composition for forming a silicon-containing film has no aromatic ring, and a contact angle of the composition for forming a silicon-containing film after curing and after the plasma treatment relative to pure water is 20 degrees or less. This can provide in a super straight used for inkjet-adaptive planarization: a transparent composition for forming a silicon-containing film that planarizes a contact surface and that provides an appropriate contact angle with a plasma treatment; a method for forming a film using the composition; and a super straight main body using the composition.

[FIGURE: NONE]